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Nanotechnologies - A guideline for ellipsometry application to evaluate the thickness of nanoscale films

Contents

Page

FOREWORD 3
INTRODUCTION 5
1 Scope 6
2 Normative references 6
3 Terms and definitions 6
3.1 General terms 6
3.2 Terms specific to this document 7
4 Measurement of ellipsometry 8
4.1 General 8
4.2 Measurement procedure 9
4.2.1 Sample preparation for system check 9
4.2.2 Experimental procedure for system check 9
4.2.3 Sample handling 9
4.2.4 Experimental procedures 9
5 Reporting data 10
6 Data analysis / interpretation of results 10
6.1 General 10
6.2 Setting analysis model 11
6.3 Data fitting and validation of analysis result 12
6.3.1 General 12
6.3.2 Data analysis method 1 – Dispersion law (Cauchy model) [6] 13
6.3.3 Data analysis method 2 – Sellmeier equation model (transparent material) [7] 13
6.3.4 Data analysis method 3 – Drude dispersion model (conductive material) [8], [9] 13
6.3.5 Data analysis method 4 – Dispersion law (classical model / Lorentz model) [8], [9] 14
6.3.6 Data analysis method 5 – Forouhi-Bloomer dispersion model [10], [11] 15
6.3.7 Data analysis method 6 – Tauc-Lorentz dispersion model (amorphous materials) [12], [13] 15
Annex A (informative) Case study: Interlaboratory comparison by using SiO_2/Si samples 17
Annex B (informative) Case study: Ellipsometry measurement of other materials 19
Bibliography 20

Figure 1 – Primary structure of ellipsometry measurement 8
Figure 2 – Flow chart of the ellipsometry data analysis 11
Figure A.1 – An example of the report form of ellipsometry measurements 17
Figure A.2 – An example of the results of the interlaboratory comparison 18
Figure A.3 – The wafer-shaped sample used for the interlaboratory comparison 18